# 304. PTB Seminar VUV and EUV Metrology

## Friday, October 20

| Time | Speaker | Title | Affiliation |
|---|---|---|---|
| **9:00** | | **Session IV: EUVL (I)** | Chair: Scholze |
| 9:00 | V. Banine | EUV Lithography now | ASML |
| 9:20 | H. Enkisch | Manufacturing and Industrialization of EUV Lithography Optics | CZ SMT |
| 9:40 | P. Pennartz | Specific Multilayer Applications in EUV Lithography machines | Rigaku |
| 10:00 | | Coffee | |
| **10:40** | | **Session V: EUVL (II)** | Chair: Laubis |
| 10:40 | N. Chkhalo | Be-based multilayers for EUV spectral range | IPM RAS |
| 11:00 | N. Böwering | Cleaning of tin-drop contaminated EUV optics by initiation of phase transformation | U Bielefeld |
| 11:20 | T. Feigl | Reflective EUV Diffusors | optiXfab |
| 11:40 | M. Mebonia | Experimental studies of the propagation of programmed buried defects into multilayer coatings | FZ Jülich |
| 12:00 | | Lunch Buffet | |
| 13:00 | | Poster & Coffee | |
| **14:00** | | **Session VI: EUV Scattering** | Chair: Soltwisch |
| 14:00 | I. Englard | Multi-dimensional metrology process control challenges for the 5nm node and below | AMIL |
| 14:20 | Y. Ekinci | EUV actinic mask inspection using coherent scattering methods | PSI |
| 14:40 | A. Fernandez Herrero | Impact of grating line roughness in the resonant diffuse scattering | PTB |
| 15:00 | | Wrap-up and Closing | |
| **15:15** | | **End of the Seminar** | |